

## Erratum: The Transition from Internal Oxidation to Continuous Film Formation during Oxidation of Dilute Ni-Si Alloys\*

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Parts of Figure 8 on p. 327 were illegible. A clearer figure appears below.

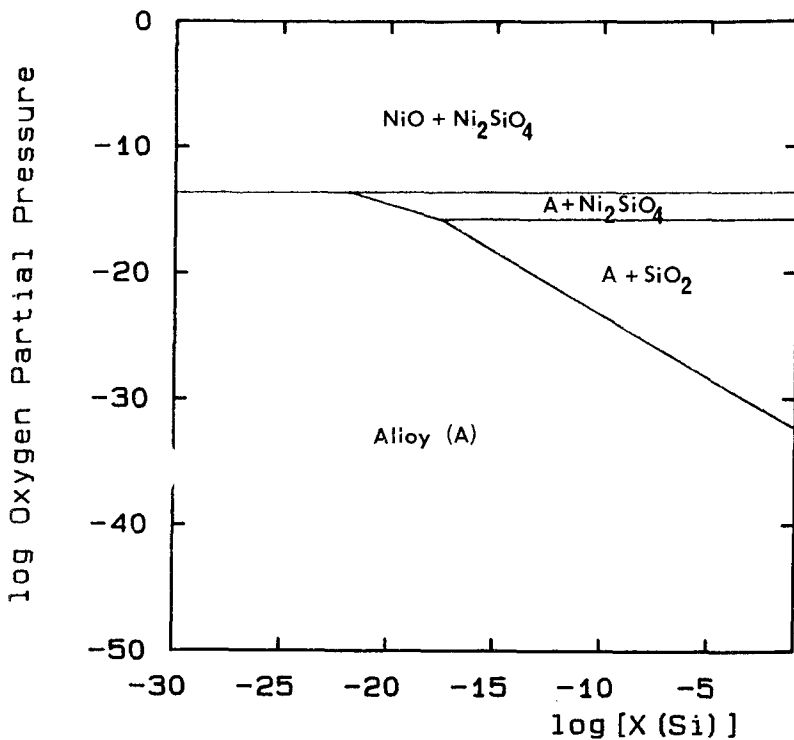


Fig. 8. Calculated stability diagram, Ni-Si-O at 800°C.

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